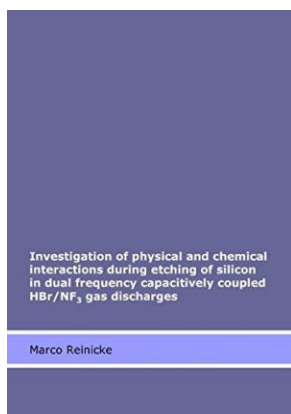


Get Book

INVESTIGATION OF PHYSICAL AND CHEMICAL INTERACTIONS DURING ETCHING OF SILICON IN DUAL FREQUENCY CAPACITIVELY COUPLED HBR/NF3 GAS DISCHARGES



Books On Demand Nov 2009, 2009. Taschenbuch. Book Condition: Neu. 213x151x20 mm. Neuware - High aspect ratio silicon etching used for DRAM manufacturing still remains as one of the biggest challenges in semiconductor fabrication, requiring well understood and characterized process fundamentals. In this study, physical and chemical interactions during etching silicon in capacitively coupled plasma discharges were investigated in detail for different HBr/NF₃ mixed chemistries for single frequency as well as dual frequency operation and medium discharge pressures inside an industrial...

Read PDF Investigation of physical and chemical interactions during etching of silicon in dual frequency capacitively coupled HBr/NF₃ gas discharges

- Authored by Marco Reinicke
- Released at 2009



Filesize: 4.35 MB

Reviews

Absolutely essential study ebook. It is probably the most amazing pdf i actually have read. Once you begin to read the book, it is extremely difficult to leave it before concluding.

-- **Enola Cormier**

Great e book and helpful one. I really could comprehend almost everything out of this composed e pdf. You are going to like how the author compose this pdf.

-- **Russel Beer III**

Absolutely essential read through book. Yes, it really is enjoy, nonetheless an interesting and amazing literature. Your daily life span is going to be transform when you comprehensive looking over this ebook.

-- **Mr. Cielo Koch II**